





Developing Standards for LED Manufacturing

DOE SSL Manufacturing Workshop June 13, 2012

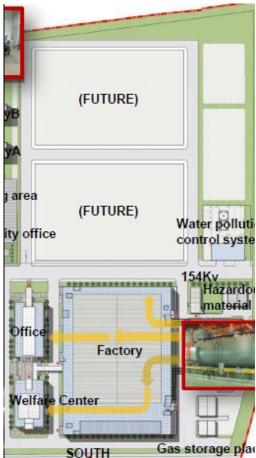


Agenda

- LED Wafer
 Manufacturing Today
 - Capacity and Equipment Spending by Region
- LED Standards
 - Wafer geometries
 - Factory automation
 - Wafer defects and impurities
 - Manufacturing safety
- Public Policy









SEMI: The Global Association

- Global Association
 ~2,000 member companies
- LED Events
 - US, Taiwan, Japan,
 Korea, China, India
- Standards
- Advocacy
- Market Research
- EHS
- Semiconductor, LED, FPD, MEMS, PV, plastic electronics, emerging markets











SEMI LED Advisory Committees

North American and Europe

China

India

Korea

Taiwan

Participating Companies (partial



















































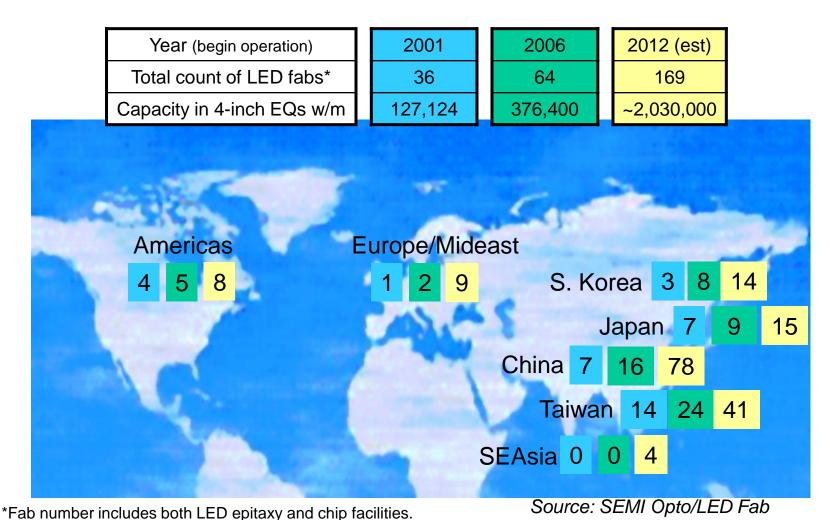






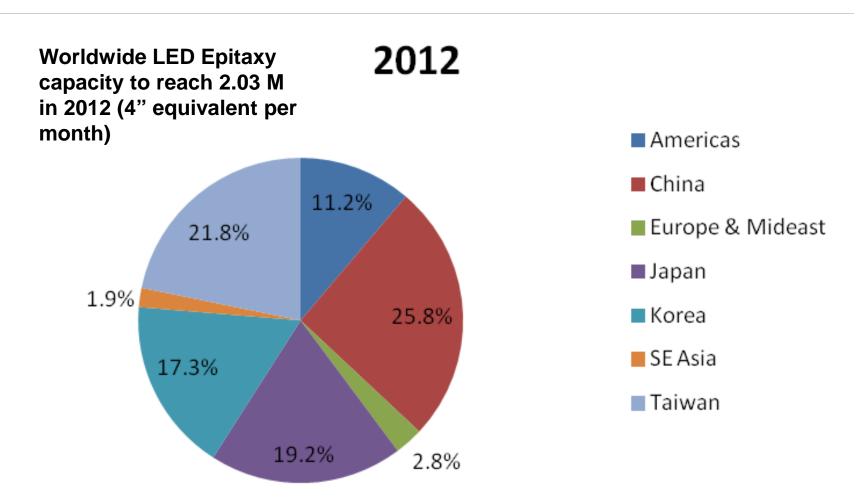
LED Dedicated Fabs Changing LED Landscape





Forecast, April 2012

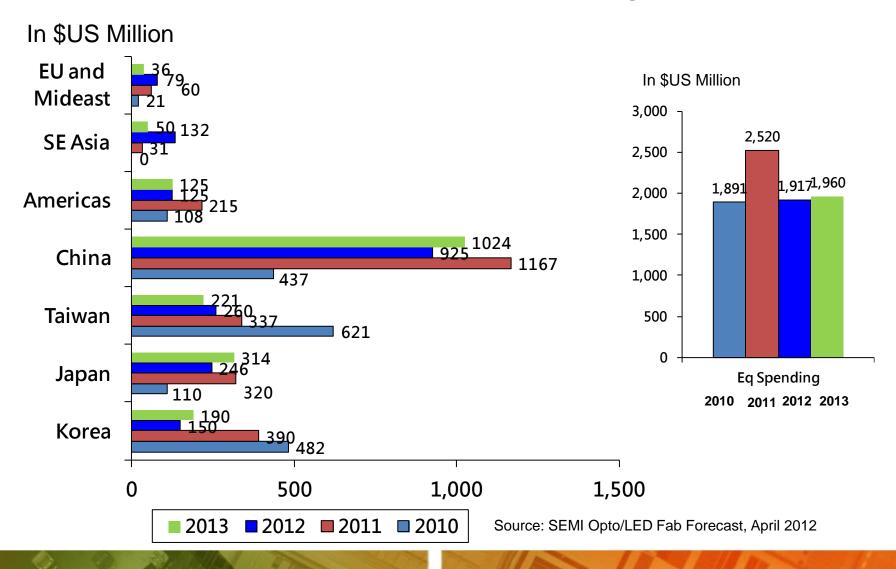
LED Fab Capacity by Region, 2012



Source: SEMI Opto/LED Fab Forecast, April 2012



LED Fab Equipment Spending





SEMI LED Standards Organization Chart

North America HB-LED Committee

Iain Black (Philips Lumileds)
Bill Quinn (Veeco)
Chris Moore (Semilab)
David Reid (Silian)

HB-LED Wafer TF

Julie Chao (Silian) David Joyce (GT Advanced Technologies)

Impurities & Defects in HB-LED Sapphire Wafers TF

Luke Glinski (GT Advanced Technologies)

HB-LED Factory Automation Interface TF

Daniel Babbs (Brooks Automation)

Jeff Felipe (Entegris)

HB-LED Assembly TF

Paul Reid (Kulicke & Soffa)

Taiwan EH&S Committee

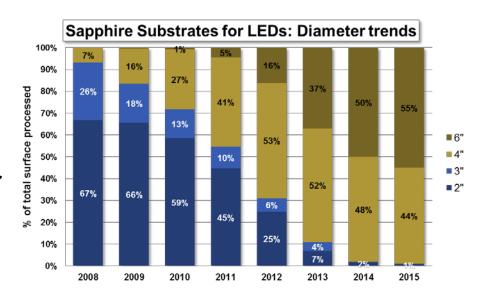
HB-LED Safety Task Force
Taiwan

Eric Lin (Epistar)



HB-LED Wafer Task Force

- Charter: Define physical geometry of wafers used in HB-LED manufacturing starting with 150 mm diameter sapphire wafers
- Critical LED cost contributor
- Enormous advantages to performing process development on standardized wafers
- Critical contingency on automation standards



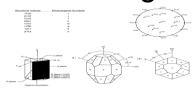
Source: Yole Developpment

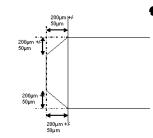


150/100 mm Wafer Standards

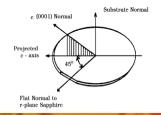
17 Key Parameters

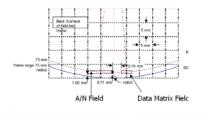
- Total Impurity Content
- Wafer ID Marking
- •Front Surface Condition
- Edge Surface Condition
- Back Surface Condition
- Diameter
- Fiducial Type
- Fiducial Dimensions
- Flat Length





- Fiducial Notch Depth & Angle
- Fiducial Orientation
- Edge Profile Template
- Thickness, Center Point
- Total Thickness Variation, Max.
- Bow and Warp, Max.
- Inclusions or Bubbles
- Dislocations
- Thermal Conductivity Uniformity





HB-LED Wafer Task Force Timeline



- July 2011- New Standard Initiative Approved
 - Doc. #5265: Specification for 150 mm Diameter Sapphire Wafers for HB-LED Applications
- Standards meetings held in US (3), Europe, and Taiwan, Japan
 - Information meetings in China, Korea
- HB-LED Sapphire Wafer Specifications
- January 2012- Proposed Wafer Standard goes to ballot
 - Feedback received for ballot 5265 suggested several opportunities for improvement
- Ballot 5265 will be reworked by the TF and will incorporate specifications for 100 mm sapphire wafers
- May 30, 2012- Ballot 5265A resubmitted for Cycle 4 voting period (May 30 – June 29)

Factory Automation Interfaces

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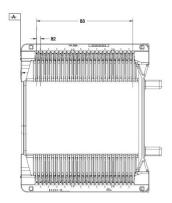
Hardware Working Group

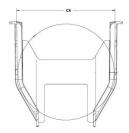
Charter:

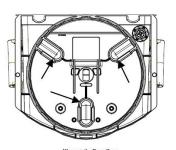
- Define physical interfaces of substrate carriers used in HB-LED manufacturing
- Define physical interfaces of process and metrology tools and of wafer / substrate carriers used in HB-LED manufacturing



- This effort will require some initial discussions around a common vision for an HB-LED factory to which these standards shall apply
- Start with 150 mm diameter wafers:
 - Cassettes
 - Shipping carriers
 - from wafer supplier to epi processor, and
 - from epi processor to front-end HB-LED device fab
- Future
 - Automation carriers
 - Process carriers







Kinematic Coupling

Factory Automation Interfaces Hardware Working Group-STATUS



- Equipment Automation TF Hardware WG
 - 150 mm Open Cassette Specification
 - Ballot proposal will specify dimensional requirements for both metal and plastic type cassettes; using SEMI E1 as a starting point
 - Moving forward with 16-capacity proposal
 - Ballot 5420 (New Standard: Specification for Cassettes for 150mm Sapphire wafers used in HB-LED manufacturing) will be submitted for the Cycle 4 voting period
 - 150 mm Load Port Interface Specification
 - Completion of draft ballot proposal by Fall 2012
 - Ballot submission in Q1 2013

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Factory Automation Interfaces Software Working Group-STATUS

- Equipment Automation TF Software WG
 - Agreed Plan for Ballot Draft Development of Software interfaces
 - Define boundary conditions for reviewing standards & reporting of required changes
 - Define Phases for reviewing standards
 - Phase 1: Basic communication standards
 - Phase 2: Extended functionalities on SECS II GEM
 - Phase 3: Interface A communication standards
 - Develop draft ballot(s) [Rev A] including Phase 1&2 until Oct 2012
 - Start of Phase 3 after Release of 1st standards version in 2013

Sapphire Impurities and Defects Task Force

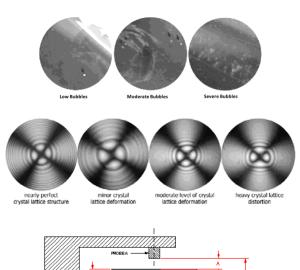


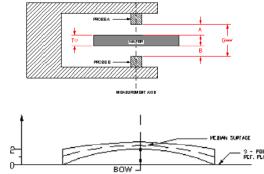
- Charter: Investigate the allowable impurities and defects in HB-LED sapphire wafers
- Scope: Define and/or measure critical impurities and defects in sapphire waters and the metrology intended to measure them.
- Objective: Create standards related to these impurities and defects for use by HB-LED sapphire wafer makers and producers of related devices.
- Topics to be considered may include, but are not limited to:
 - Bulk Crystal Defects
 - Bulk Crystal Impurities
 - Surface Defects
 - Surface Impurities



Sapphire Impurities and Defects

- Lineages (Low Angle Grain Boundary)
- Bubbles
- Lattice Distortion
- Twins Inclusions TTV Total Thickness Variation
- Bow
- Warp
- EPD Count







Known Metrology and Tests

- OHT Polarized Light Inspection (Optical Homogeneity Technique)
- **High Intensity Light Inspection**
- Polarized Light Microscopy
- X-Ray
- **GDMS** (Glow Discharge Mass Spectroscopy)
- Surface Profilometers
- Laser Interferometry
- EPD "Etch Pit Density"
- **Automated Laser Defect Inspection**
- **Atomic Force Microscopy**
- **Acoustic Microscopy**





KLA Tencor Candela 6250

PANalytical X'Pert





Dimension. Brukner







Chapman MPT1000

Sapphire Impurities and Defects Task Force



Status

- Reviewed proposed survey document which will identify:
 - sapphire wafer defects that are relevant or important to HB-LED manufacturing
 - inspection techniques can be applied to identify, measure or prevent the identified defect list



Taiwan Safety Task Force

Charter:

 The objective is to develop EHS (Environmental health and safety) technical standard specifications and guidelines related to LED (light emitting diodes) manufacturing

Scope:

 The activities of the task force will result in the development of an EHS industry standard which equipment suppliers, raw material suppliers, module makers and other involved parties can find conformity.

Initial work will focus on:

- Surveying current LED equipment was covered by SEMI S2 or not.
- Developing EHS guidelines for manufacturing equipment of LED industry.

Future works may include:

- Establishing equipment safety event database
- Collecting and analyzing the data of safety notice and SEMI reports which were certified by third party
- Developing SEMI EHS standards for LEDs manufacturing.

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US Policy

- Increase DOE funding for both R&D and manufacturing infrastructure development of the U.S. LED/SSL industry
- Establish the R&D tax credit on a long-term basis to assure LED/SSL manufacturers greater consistency in tax and investment planning
- Revive the Advanced Energy Manufacturing Tax Credit (MTC), and creation of a federal Green Bank to supplement LED and other green energy projects, particularly for manufacturing.
- Work with foreign counterparts and the WTO to develop a strong, effective and enforceable rules-based international trading system that promotes free and open trade.
- Support reasonable export control work that applies to LED/SSL in the movement to decontrol MOCVD tools.



Thank You

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